

**巨玻固能(苏州)薄膜材料有限公司 Jubo Guneng(SuZhou)Thin Film Materials Co., Ltd.**

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|------------------------------|-------------------------------|--|
| <b>Material材料名称:</b>         | SiO <sub>2</sub> 二氧化硅         |  |
| <b>Article No.产品编码:</b>      | BoSE-18-58                    | 079.18.58  |
| <b>Delivery Form产品规格:</b>    | 1.5-3.0mm                     | UV   |
| <b>Material Properties:</b>  | Chemical Formula分子式:          | SiO <sub>2</sub>   |
| <b>材料特征:</b>                 | Purity纯度:                     | 99.99%   |
|                              | Typical Impurities杂质类型 [ppm]: | Ca<90 Fe,Si,Ce<30,<br>Pr,La,Nd,Y,Gd<10                           |
|                              | Density-theoretical 理论密度:     | 2.3 g/cm <sup>3</sup>  |
|                              | Melting Point熔点:              | 1730 °C  |
|                              | Hydroxyl content羟基含量:         | <30ppm   |
| <b>Test Parameters:</b>      | Coating Equipment镀膜设备:        | ZSS 700  |
| <b>测试参数:</b>                 | Evaporation Source蒸发源:        | Electron Beam Gun电子枪   |
|                              | Substrate Temp.基底温度:          | 250 °C   |
|                              | Process Gas充气压力:              |  |
|                              | Evaporation Rate蒸发速率:         | 0.3-0.5 nm/s   |
| <b>Thin Film Properties:</b> | Chemical Composition化学成分:     | SiO <sub>2</sub>   |
| <b>薄膜参数:</b>                 | Refractive Index折射率:          | 1.46 (520nm <λ< 580 nm)  |
| <b>Remark</b>                | Transparency Range透明区域:       | 200nm~9μm  |
| <b>备注:</b>                   | Melting Behaviors蒸发习性:        | Film densification, good at chemical stability.<br>成膜致密, 化学稳定性好。 |

**Material Certification声明:**

We certify, the material is in compliance with the specifications stated above.

我们证明, 该材料符合上述规范。

**Date 日期:** 2021-1-19  
**Certificate No.证书编号:** JBSE-Specification 079.18.58